

Measurement of: Fabrication of micron sized patterns using Ar ion milling

Equipment: Argon Ion Milling System

Photograph:



Basic Principle: This facility is used for fabrication of micron sized patterns using Ar ion. It includes turbo pumping station for a clean and oil free operation, rotating sample stage with water cooling arrangement for uniform milling, gridded ion source with filament neutralizer, 4 inch diameter collimated ion beam with 120 mA beam current and 100 – 1200 operating voltage range.

Capabilities: Down to 10 micron feature size can be realized

Sample Requirement: Thin film samples